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IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Hiroshi ITATANI et al. Conf.: 9966
Appl. No.: 09/980,212 Group: 1752
Filed: March 18, 2002 Examiner: R. Ashton
For: METHOD FOR FORMING POLYIMIDE PATTERN USING
PHOTOSENSITIVE POLYIMIDE AND COMPOSITION THEREFOR

AMENDMENT UNDER 37 C.F.R. § 1.312

HANDCARRY TO:
U.S. Patent and Trademark Office
2011 South Clark Place
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April 21, 2004

Sir:

Pursuant to the provisions of 37 C.F.R. § 1.312, the following amendments and remarks are respectfully submitted in connection with the above-identified application. It is respectfully requested that the following amendments be entered without withdrawing the application from issue.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 7 of this paper.

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15. (Canceled)

16. (Previously Presented) A method for forming negative-type pattern of polyimide comprising coating a substrate with the polyimide recited in claim 1; selectively irradiating the polyimide with an actinic ray, the irradiated regions constituting a desired pattern; and developing the irradiated polyimide with an alkaline solution to dissolve the non-irradiated regions.

17. (Original) The method according to claim 16, wherein said actinic ray is electron beam.

18. (Canceled)